





Metallic ion implantation device.**Publication number:** DE3884899 (T2)**Publication date:** 1994-04-28**Inventor(s):** BERNARDET HENRI SOCIETE CIVILE [FR]; THIEBAUT
CHANTAL SOCIETE CIVIL [FR]**Applicant(s):** PHILIPS NV [NL]**Classification:****- international:** *H01J37/06; H01J27/08; H01J37/08; H01J37/317; H01J37/06;
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H01J27/08***- European:** H01J27/08; H01J37/08; H01J37/317A**Application number:** DE19883884899T 19880721**Priority number(s):** FR19870011130 19870805**Also published as:** EP0307017 (A1) EP0307017 (B1) US4994164 (A) JP1097363 (A) FR2619247 (A1)

Abstract not available for DE 3884899 (T2)

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Metallurgical implanter of metal ions having a large emissive surface area, significant flux and adjustable implantation depth comprising, inside an implantation chamber kept evacuated, at least one vacuum-arc ion source (1, 2, 3, 4) from which the ions (5) are extracted and projected onto a target (9) by means of an extracting and focusing electrode (6, 7) and of an acceleration electrode (8) which are polarised to very high and to low voltage respectively. The target (9) bombarded with the ion stream emits a flux of secondary electrons which are repelled by a suppressor electrode (10) which is negatively polarised relative to the earthed target. <??>Application in metallurgy.

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